

## **ABSTRACT OF THE DISCLOSURE**

A semiconductor device having regions for forming a plurality of functional blocks and a region for forming wiring 5 layers for connecting the functional blocks, wherein each of the regions for forming the functional blocks includes a multilayer wiring, and the region for forming the wiring layers for connecting adjacent functional blocks includes a coaxial line comprised of a signal line and a ground line surrounding 10 the signal line via an insulating film.